

ABSTRACT OF THE DISCLOSURE

Alignment Mark System for Mass Transport Processes

5

A technique for creating alignment feature in mass transported substrates yields alignment features that can be located with high degrees of accuracy. Specifically, structures such as concave or convex lenses are created that yield a light pattern in transmission or reflection when the part of the substrate is imaged or a plane near the substrate is imaged.

10 This light pattern is then used to align the substrate during subsequent lithography or packaging processes.